

National Semiconductor Translation and Innovation Centre (Power Electronics) Technical Capabilities

SiC Device Design and Simulation	Design and Simulation	- Calibration and simulation of in-house models to match experimental results of a 1.2 kV rated Trench MOSFET - Development of models for device architectures such as: planar, trench, super-junction and SiC IGBT structures
	SiC Epitaxy	- Max thickness: $74.2 \mu\text{m} \pm 1.2\%$ - Defect density: $0.2 / \text{cm}^2$
	SiC Gate-Stack Formation	- Low Dit: $\sim 10^{11} \text{ cm}^{-2} \text{ eV}^{-1}$ - Channel mobility: $61 \text{ cm}^2/\text{V}\cdot\text{s}$
Process Capabilities	Channeling Implant	- Energy: Up to 960 keV - Species: Al, B, P, N, Ar - Substrate temperature: 25 to 500 °C - Tilt angle: 0 to 60° - Twist angle: 0 to 270°
	Liquid Cooling	Thermal resistance: $0.1 \text{ }^\circ\text{C}/\text{W}$
	Power Cycling	- Loop inductance: 10 nH - Power cycling time: 50 K cycles - Thermal cycling: 1 K cycles - High-temperature storage: 1000 hrs
SiC Power Module Packaging	Wafer Level Test System	- Max voltage: 10 kV - Max current: 600 A
	Cryogenic Measurement System	- Superconducting magnet max: 25.0 kOe (2.5 T) - Min temperature: 10 K
	Double-Pulse Test System	- Package type: TO-247 - Max voltage: 1.2 kV - Max current: 1000 A
	High-Temperature Reliability System	- Dynamic HTGB - Dynamic HTRB - Dynamic H3TRB
	Short Circuit Withstand Time Characterisation	- Max voltage: 1.2 kV - Max pulse current: 3000 A
	Unclamped Inductive Switching Characterisation	- Max voltage: 2.5 kV - Max current: 200 A
Power Device Electrical Characterisation		



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Demonstrated Devices	SiC Planar and Trench MOSFETs	- Breakdown voltage: 1.2 kV $R_{ON,SP}$: 1.6 mΩ·cm² - Channel mobility: 61 cm²/V·s
	SiC Super-Junction MOSFETs	- Breakdown voltage: 1.7 kV - Super-junction depth: 14 μm
	SiC PIN Diodes	Breakdown Voltage: 7.8 kV

